

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Watanabe et al.
Appl. No.	:	10/574,073
Filed	:	March 30, 2006
For	:	RESIST COMPOSITION FOR ELECTRON BEAM OR EUV
Examiner	:	Walke, Amanda
Group Art Unit	:	1752

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION**Mail Stop AF**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **December 17, 2007**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 6 of this paper.